

Title (en)

ELECTROLYTE FOR GALVANIC DEPOSITION OF ALUMINIUM

Publication

EP 0084816 A3 19840606 (DE)

Application

EP 83100245 A 19830113

Priority

DE 3202265 A 19820125

Abstract (en)

[origin: US4417954A] An organometallic electrolyte for the electrodeposition of aluminum is described which exhibits high throwing power as well as high conductivity and good solubility and is commercially readily accessible. For this purpose, the invention provides an electrolyte of a formula based upon an organometallic complex of potassium, rubidium or cesium fluoride in combination with a series of organometallic aluminum compounds.

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C25D 3/44 (2006.01); **C25D 3/66** (2006.01)

CPC (source: EP US)

C25D 3/44 (2013.01 - EP US)

Citation (search report)

- [AD] DE 1047450 B 19581224 - E H KARL ZIEGLER DR DR
- [A] US 4101386 A 19780718 - DOTZER RICHARD, et al

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EP0402760A1; EP0504705A1; EP1927680A1; EP0504704A1; EP0267534A1; NL8602856A; DE19716495C1; EP0505886A1; DE19716493A1; DE19716493C2; EP0402761A1; DE102007018489A1; WO2010106072A2; WO2008064954A3; WO03102276A1; WO9848082A1

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